

Applicant: Utsumiya, et al.
 Serial N.: 09/761,025
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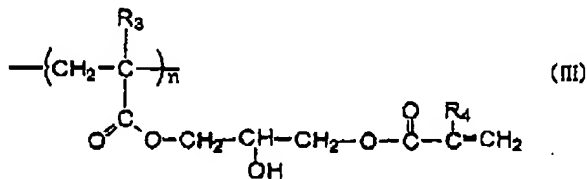
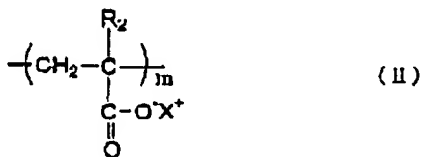
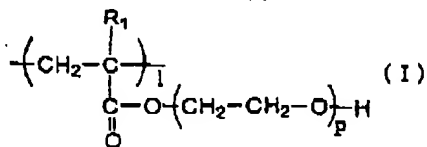
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Claim Amendments:

1. (Canceled)
2. (Canceled)
3. (Canceled)
4. (Canceled)
5. (Withdrawn)
6. (Withdrawn)
7. (Withdrawn)
8. (Withdrawn)
9. (Withdrawn)
10. (Withdrawn)

11. (New) A photosensitive composition comprising, as a component, a polymer compound, and an alkali agent for neutralization, wherein;

the polymer compound contains monomer units represented by formulas (I) to (III) and a monomer unit other than monomer units represented by formulas (I) to (III) in an amount of q mol%;



wherein each of R_1 to R_4 is hydrogen and/or a methyl group; p represents an integer between 1 to 10 inclusive; x represents hydrogen;

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the compositional proportions of the monomer units falling with the following ranges: $2 \text{ mol\%} \leq l \leq 73 \text{ mol\%}$; $8 \text{ mol\%} \leq m \leq 83 \text{ mol\%}$; $15 \text{ mol\%} \leq n \leq 80 \text{ mol\%}$; $0 \text{ mol\%} \leq q \leq 10 \text{ mol\%}$; and $(l + m + n + q) = 100 \text{ mol\%}$.

12. (New): A photosensitive composition according to Claim 11, which contains water as a solvent.

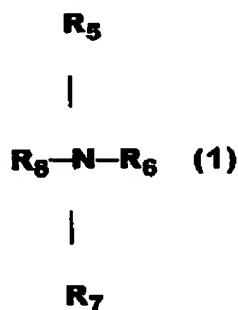
13. (New): A photosensitive composition according to Claim 11, which contains a polymerizable monomer.

14. (New): A photosensitive composition according to Claim 11, which contains a colorant.

15. (New): A photosensitive composition according to Claim 11, which contains at least one of a photopolymerization initiator and a photosensitizer.

16. (New): A photosensitizer composition according to claim 11, the alkali agent for neutralization is at least one species selected from the group consisting of an inorganic alkaline compound or an organic amine or ammonium.

17. (New): A photosensitive composition according to claim 11, a residue of the ammonium is represented by formula (1):



wherein each of R_5 to R_8 represents hydrogen, a C1-C3 alkyl group, or a C1-C3 alkanol group; and a plurality of Xs any be the same or different from one another.

18. (New) A pattern formation method comprising forming a coating film by use of a photosensitive composition as recited in claims 11-17, and developing by use of a neutral developer such as water.